

1. Record Nr.	UNINA9910450116103321
Titolo	Surface contamination and cleaning . Volume 1 // edited by Kash L. Mittal
Pubbl/distr/stampa	Boca Raton, FL : , : CRC Press, an imprint of Taylor and Francis, , 2003
ISBN	0-429-08796-9 1-280-46543-3 9786610465439 1-4175-7784-3 90-474-0328-2 1-60119-232-0
Edizione	[First edition.]
Descrizione fisica	1 online resource (373 p.)
Disciplina	620/.44
Soggetti	Surface contamination Electronic books.
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references.
Nota di contenuto	Contents; Preface; Mapping of surface contaminants by tunable infrared-laser imaging; Monitoring cleanliness and defining acceptable cleanliness levels; Tracking surface ionic contamination by ion chromatography; A new method using MESERAN technique for measuring surface contamination after solvent extraction; Methods for pharmaceutical cleaning validations; Influence of cleaning on the surface of model glasses and their sensitivity to organic contamination; Decontamination of sensitive equipment; The fundamentals of no-chemistry process cleaning Development of a technology for generation of ice particlesCleaning with solid carbon dioxide pellet blasting; Development of a generic procedure for modeling of waterjet cleaning; Experimental and numerical investigation of waterjet derusting technology; Practical applications of icejet technology in surface processing; Correlating cleanliness to electrical performance; Qualifying a cleaning system for space flight printed wiring assemblies; Investigation of modified SC-1 solutions for silicon wafer cleaning

Performance qualification of post-CMP cleaning equipment in a semiconductor fabrication environment
 Spatial and temporal scales in wet processing of deep submicrometer features;
 Microdenier fabrics for cleanroom wipers;
 Fine particle detachment studied by reflectometry and atomic force microscopy;
 Dust removal from solar panels and spacecraft on Mars;
 Laser cleaning of silicon wafers: Prospects and problems;
 Particle removal using resonant laser detachment;
 The future of industrial cleaning and related public policy-making

Sommario/riassunto

This volume documents the proceedings of the International Symposium on Surface Contamination and Cleaning, held in Newark, New Jersey, May 23-25, 2001. A new method using MESERAN technique for measuring surface contamination after solvent extraction
 B. Newton
 Because of the importance of this topic in many technological areas, tremendous efforts have been devoted to devise novel and more efficient ways to monitor, analyse and characterize contamination on surfaces as well as ways to remove such contamination from a wide variety of surfaces. The technological areas where surface contamination has always been a *bete noire* and thus surface cleaning is of cardinal importance are too many and range from aerospace to microelectronics to biomedical.
 C. Beaudry and S. Verhaverbeke
 C. LeBlanc
 Cleaning with solid carbon dioxide pellet blasting
 Correlating cleanliness to electrical performance
 D. Ottesen, S. Sickafoose, H. Johnsen, T. Kulp, K. Armstrong, S. Allendorf and T. Hoffard
 D.V. Shishkin, E.S. Geskin and B. Goldenberg
 D.V. Shishkin, E.S. Geskin and B. Goldenberg
 Decontamination of sensitive equipment
 Development of a technology for generation of ice particles
 Development of a generic procedure for modeling of waterjet cleaning
 Dust removal from solar panels and spacecraft on Mars
 Experimental and numerical investigation of waterjet derusting technology
 F.C. Young
 Feiler and J. Ralston
 Fine particle detachment studied by reflectometry and atomic force microscopy
 H.J. Kaiser
 Influence of cleaning on the surface of model glasses and their sensitivity to organic contamination
 Investigation of modified SC-1 solutions for silicon wafer cleaning
 J. Skoufis and D.W. Cooper
 J.B. Durkee II
 J.K. Kirk Bonner and A. Mehta
 K. Babets and E.S. Geskin
 K. Babets, E.S. Geskin and B. Goldenberg
 K. Kearney and P. Hammond
 Laser cleaning of silicon wafers: Prospects and problems
 M. Mosbacher, V. Dobler, M. Bertsch, H.-J. Mnzer, J. Boneberg and P. Leiderer
 M. Olim
 M.G. Benkovich and J.L. Anderson
 M.K. Chawla
 M.T. Andreas
 Mapping of surface contaminants by tunable infrared-laser imaging
 Methods for pharmaceutical cleaning validations
 Microdenier fabrics for cleanroom wipers
 Monitoring cleanliness and defining acceptable cleanliness levels
 Particle removal using resonant laser detachment
 Performance qualification of post-CMP cleaning equipment in a semiconductor fabrication environment
 Practical applications of icejet technology in surface processing
 Qualifying a cleaning system for space flight printed wiring assemblies
 R. Kaiser and K. Haraldsen
 S. Trigwell, M.K. Mazumder, A.S. Biris, S. Anderson and C.U. Yurteri
 Spatial and temporal scales in wet processing of deep submicrometer features
 T. Munson
 The fundamentals of no-chemistry process cleaning
 The future of industrial cleaning and related public policy-making
 This volume contains a total of 24 papers, all rigorously peer reviewed and revised before inclusion, which deal with all kinds of contaminations on a host of surfaces. The topics covered include: mapping of surface contaminants; various techniques for cleaning surfaces; various techniques for monitoring level of cleanliness; acceptable cleanliness levels; ionic contamination; pharmaceutical cleaning validations; cleaning of glass surfaces; decontamination of sensitive equipment; no-chemistry process cleaning; waterjet cleaning;

cleaning with solid carbon dioxide pellet blasting; cleanroom wipers; dust removal from solar panels and spacecraft on Mars; laser cleaning of silicon surfaces; particle removal; implications of surface contamination and cleaning; and future of industrial cleaning and related public policy-making. Tracking surface ionic contamination by ion chromatography W. Birch, S. Mechken and A. Carr.

2. Record Nr.	UNISALENTO991004185679707536
Autore	Bianucci, Piero <1944- >
Titolo	Invito alla lettura di Raffaello Brignetti / Piero Bianucci
Pubbl/distr/stampa	Milano : Mursia, 1974
Descrizione fisica	153 p. ; 17 cm
Collana	Invito alla lettura ; 26
Disciplina	853.91
Soggetti	Brignetti, Raffaello Brignetti, Raffaello
Lingua di pubblicazione	Italiano
Formato	Materiale a stampa
Livello bibliografico	Monografia